Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1129	defects same silicon same copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:26
S2	28	electrolyte and bath and S1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 08:00
S3	99	d-defects	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 08:35
S4	62	copper and S3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 08:36
S5	2	(electro or electrolyte) and S4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 08:36
S6	1	("5783495").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/03/02 08:37
S7	8	("5980720").URPN.	USPAT	OR .	ON	2005/03/02 08:39
S8	32919	(slot or slots) and copper	USPAT	OR	ON	2005/03/02 08:43
S9	0	S3 and S8	USPAT	OR	ON	2005/03/02 08:41
S10	1121	copper adj bath	USPAT	OR	ON	2005/03/02 08:42
S11	818	(wafer or substrate) and S10	USPAT	OR	ON	2005/03/02 08:42
S12	47	(slot or slots) and S11	USPAT	OR	ON	2005/03/02 08:43
S13	29	("3716462").URPN.	USPAT	OR	ON	2005/03/02 09:34
S14	4108	kim.in. and copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 10:48

	γ	<del> </del>			T	
S15	23	decoration and S14	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 10:53
S16	1740	(438/14).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/03/02 10:54
S17	22	(438/441).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/03/02 12:23
S18	1412	(438/687).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/03/02 12:26
S19	232	(electrolyte or electrolytic or electrodeless) and S18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2005/03/02 12:27

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FILE LAST UPDATED: 28 FEB 2005 <20050228/UP>
FILE COVERS 1969 TO DATE.

<<< SIMULTANEOUS LEFT AND RIGHT TRUNCATION AVAILABLE IN
THE BASIC INDEX >>>

=> s copper

L1 142605 COPPER

=> s silicon

L2 327234 SILICON

=> s defects

L3 116900 DEFECTS

=> s slots

L4 8159 SLOTS

=> s 11 and 12 and 13 and 14

L5 0 L1 AND L2 AND L3 AND L4

=> s copper bath

142605 COPPER 12284 BATH

L6 47 COPPER BATH

(COPPER (W) BATH)

=> s 13 and 16

L7 0 L3 AND L6

=> s analyzing defects

50370 ANALYZING 116900 DEFECTS

L8 8 ANALYZING DEFECTS

(ANALYZING(W) DEFECTS)

=> d 18 1-8

L8 ANSWER 1 OF 8 INSPEC (C) 2005 IEE on STN

FOIL Text

AN 2004:8284130 INSPEC DN B2005-03-2550G-041

TI Simulation of photoresist thermal flow process with viscous flow model.

AU Won-Young Chung; Tai-Kyung Kim; Yero Lee (Semicond. R&D Center, Samsung Electron., Gyeonggi-Do, South Korea); Jin-Young Yoon; Hyun-Woo Kim; Young-Kwan Park; Jeong-Taek Kong

SO Japanese Journal of Applied Physics, Part 1 (Regular Papers, Short Notes & Review Papers) (Sept. 2004) vol.43, no.9A, p.6020-5. 13 refs.

Published by: Japan Soc. Appl. Phys

CODEN: JAPNDE ISSN: 0021-4922

SICI: 0021-4922(200409)43:9AL.6020:SPTF;1-I

DT Journal

TC Practical; Theoretical; Experimental

CY Japan

## LA English

L8 ANSWER 2 OF 8 INSPEC (C) 2005 IEE on STN



AN 2004:8128784 INSPEC DN B2004-11-2550G-163

TI Simulation technique for the PR flow process using a new viscous flow model [photoresist].

AU Won-Young Chung; Tai-Kyung Kim; Jin-Young Yoon; Hyun-Woo Kim; Young-Kwan Park; Jeong-Taek Kong (Semicond. R&D Center, Samsung Electron. Co. Ltd., Gyeonggi-Do, South Korea)

SO Proceedings of the SPIE - The International Society for Optical Engineering (2004) vol.5376, no.1, p.975-82. 11 refs. Published by: SPIE-Int. Soc. Opt. Eng

Price: CCCC 0277-786X/04/\$15.00 CODEN: PSISDG ISSN: 0277-786X

SICI: 0277-786X(2004)5376:1L.975:STFP;1-R

Conference: Advances in Resist Technology and Processing XXI. Santa Clara, CA, USA, 23-24 Feb 2004

DT Conference Article; Journal

TC Practical; Theoretical; Experimental

CY United States

LA English

L8 ANSWER 3 OF 8 INSPEC (C) 2005 IEE on STN

## FOIL Text

AN 2001:6962873 INSPEC DN A2001-15-8140N-033

TI The influence of crack-like defects on the tensile strength of an open-cell aluminum foam.

AU Andrews, E.W.; Gibson, L.J. (Dept. of Mater. Sci. & Eng., MIT, Cambridge, MA, USA)

SO Scripta Materialia (17 April 2001) vol.44, no.7, p.1005-10. 6 refs. Doc. No.: S1359-6462(01)00673-X

Published by: Elsevier for Board of Directors of Acta Metall

Price: CCCC 1359-6462/2001/\$20.00 CODEN: SCRMBU ISSN: 1359-6462

SICI: 1359-6462(20010417)44:7L.1005:ICLD;1-G

DT Journal

TC Experimental

CY United States

LA English

L8 ANSWER 4 OF 8 INSPEC (C) 2005 IEE on STN



AN 1997:5587190 INSPEC DN A9713-6848-002; B9707-2530F-005

TI Effective KOH etching prior to modified Secco etching for analyzing defects in thin bonded silicon on insulator (SOI) wafers.

AU Mitani, K.; Aga, H.; Nakano, M. (Isobe R&D Center, Gunma, Japan)

SO Japanese Journal of Applied Physics, Part 1 (Regular Papers, Short Notes & Review Papers) (March 1997) vol.36, no.3B, p.1646-9. 10 refs.

Published by: Publication Office, Japanese Journal Appl. Phys
CODEN: JAPNDE ISSN: 0021-4922

SICI: 0021-4922(199703)36:3BL.1646:EEPM;1-K

Conference: 1996 International Conference on Solid State Devices and Materials (SSDM'96). Yokohama, Japan, 26-29 Aug 1996

DT Conference Article; Journal

TC Experimental

CY Japan

## LA English

L8 ANSWER 5 OF 8 INSPEC (C) 2005 IEE on STN



- AN 1994:4825581 INSPEC DN A9501-6170-001
- TI Modeling the energy of formation of defects of various dimensionalities in crystals of intermetallic compounds.
- AU Starostenkov, M.D.; Dmitriev, S.V.; German, V.G. (Polzunov Altai State Univ., Barnaul, Russia)
- SO Crystallography Reports (Sept.-Oct. 1994) vol.39, no.5, p.720-4. 6 refs. Price: CCCC 1063-7745/94/3905-0720\$10.00

CODEN: CYSTE3 ISSN: 1063-7745

Translation of: Kristallografiya (Sept.-Oct. 1994) vol.39, no.5, p.798-802. 6 refs.

CODEN: KRISAJ ISSN: 0023-4761

- DT Journal; Translation Abstracted
- TC Theoretical
- CY Russian Federation; Russian Federation
- LA English

L8 ANSWER 6 OF 8 INSPEC (C) 2005 IEE on STN

## Foll Text

- AN 1993:4454228 INSPEC DN B9309-4360-005
- TI Digital laser microscope for real-time defect imaging and review.
- AU Worster, B.W. (Ultrapointe Corp., Santa Clara, CA, USA); Politzer, B.A.
- SO Solid State Technology (May 1993) vol.36, no.5, p.55-6, 59. 2 refs. CODEN: SSTEAP ISSN: 0038-111X
- DT Journal
- TC Application; Practical
- CY United States
- LA English

L8 ANSWER 7 OF 8 INSPEC (C) 2005 IEE on STN



- AN 1990:3720088 INSPEC DN B90060830
- TI Technique for failure analysis of tantalum capacitors.
- AU Macdonald, M.A.; Brindel, F.; Sousa, D. (Sprague Electr. Co., Sanford, ME, USA)
- SO 10th Capacitor and Resistor Technology Symposium. CARTS '90 Huntsville, AL, USA: Components Technol. Inst, 1990. p.29-34 of 208 pp. 3 refs.

Conference: San Francisco, CA, USA, 26-29 March 1990 Sponsor(s): Components Technol. Inst.; IEEE

- DT Conference Article
- TC Practical; Experimental
- CY United States
- LA English
- L8 ANSWER 8 OF 8 INSPEC (C) 2005 IEE on STN



- AN 1990:3681141 INSPEC DN B90052141; C90051710
- TI Algorithm for comparing fragments of images of two crystals for monitoring integrated circuit appearance.
- AU Ivanov, V.A.; Kosykh, V.P.
- SO Optoelectronics, Instrumentation and Data Processing (1989) no.2, p.29-34. 8 refs.

```
Price: CCCC 8756-6990/89/$20.00
     CODEN: OIDPE4 ISSN: 8756-6990
     Translation of: Avtometriya (1989) no.2, p.29-34. 8 refs.
     CODEN: AVMEBI ISSN: 0320-7102
DT
     Journal; Translation Abstracted
TC
     Application; Practical
CY
     USSR; United States
LА
     English
=> s d-defects
        296296 D
        116900 DEFECTS
L9
            85 D-DEFECTS
                 (D(W) DEFECTS)
=> s 11 and 19
             7 L1 AND L9
L10
=> d 110 1-7
L10 ANSWER 1 OF 7 INSPEC (C) 2005 IEE on STN
            N 1888 8 8
   Full
          Text
ΑN
     1998:6068361 INSPEC
                              DN A9823-8110F-013; B9812-0510-026
TТ
     D-defects and metal-related flow patterns.
ΑU
     Kissinger, G.; Morgenstern, G.; Richter, H. (Inst. fur Semicond. Phys.,
     Frankfurt, Germany); Vanhellemont, J.; Graf, D.; Lambert, U.; Von Ammon,
     W.; Wagner, P.
     Proceedings of the Symposium on Crystalline Defects and Contamination:
so
     Their Impact and Control in Device Manufacturing II
     Editor(s): Kolbesen, B.O.; Claeys, C.; Stallhofer, P.; Tardiff, F.
     Pennington, NJ, USA: Electrochem. Soc, 1997. p.32-9 of x+518 pp. 13 refs.
     Conference: Paris, France, 31 Aug-5 Sept 1997
     ISBN: 1-56677-175-7
     Conference Article
DT
TC
     Practical; Experimental
CY
     United States
LΑ
     English
     ANSWER 2 OF 7 INSPEC (C) 2005 IEE on STN
   Text
                              DN A9204-6170B-002
AN
     1992:4065619 INSPEC
ΤI
     Identification of vacancy clusters in FZ-Si crystals.
ΑU
     Kitano, T. (VLSI Dev. Div., NEC Corp., Kanagawa, Japan)
     Physica Status Solidi A (16 Oct. 1991) vol.127, no.2, p.341-7. 16 refs.
SO
     CODEN: PSSABA ISSN: 0031-8965
     Journal
DT
TC
     Experimental
CY
     Germany, Federal Republic of
LА
     English
L10 ANSWER 3 OF 7 INSPEC (C) 2005 IEE on STN
           Full
          Text
ΑN
     1991:3945455 INSPEC
                              DN A91104121
     Behavior of point defects in FZ silicon crystals.
ΤI
ΑU
     Abe, T.; Kimura, M. (Isobe R&D Center, Gunma, Japan)
SO
     Proceedings of the Sixth International Symposium on Silicon Materials
```

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Science and Technology: Semiconductor Silicon 1990
    Editor(s): Huff, H.R.; Barraclough, K.G.; Chikawa, J.-I.
    Pennington, NJ, USA: Electrochem. Soc, 1990. p.105-16 of xix+1090 pp. 23
     refs.
    Conference: Montreal, Que., Canada, 7-11 May 1990
    Sponsor(s): Electrochem. Soc
DT
    Conference Article
TC
    Experimental
    United States
CY
LΑ
    English
L10 ANSWER 4 OF 7 INSPEC (C) 2005 IEE on STN
       Full
   Text...
    1988:3115574 INSPEC
                             DN A88054503
AN
    Investigation of D defects in silicon by X-ray topography.
TΙ
ΑU
    Vysotskaya, V.V.; Gorin, S.N.; Sorokin, L.M.; Sheikhet, E.G. (A.A. Baikov
    Inst. of Metall., Acad. of Sci., Moscow, USSR)
SO
    Soviet Physics - Solid State (June 1987) vol.29, no.6, p.1068-70. 13 refs.
    Price: CCCC 0038-5654/87/061068-03$03.90
    CODEN: SPSSA7 ISSN: 0038-5654
    Translation of: Fizika Tverdogo Tela (June 1987) vol.29, no.6, p.1858-61.
    13 refs.
    CODEN: FTVTAC ISSN: 0367-3294
DT
    Journal; Translation Abstracted
TC
    Experimental
CY
    USSR; United States
LA
    English
L10 ANSWER 5 OF 7 INSPEC (C) 2005 IEE on STN
            Text
           AN
     1987:2832599 INSPEC
                             DN A87032340
TI
    Impurity effect on formation of microdefects during silicon crystal
     growth.
    Chikawa, J. (Nat. Lab. for High Energy Phys., Tsukuba, Japan)
ΑU
    Proceedings of the Fifth International Symposium on Silicon Materials
SO
     Science and Technology: Semiconductor Silicon 1986
     Editor(s): Huff, H.R.; Abe, T.; Kolbesen, B.
     Pennington, NJ, USA: Electrochem. Soc, 1986. p.61-75 of xiv+1096 pp. 27
     refs.
    Conference: Boston, MA, USA, 5-9 May 1986
    Sponsor(s): Electrochem. Soc
    Conference Article
DT
TC
    Experimental
CY
    United States
LΑ
    English
L10 ANSWER 6 OF 7
                   INSPEC
                          (C) 2005 IEE on STN
            1983:2139319
                  INSPEC
                             DN A83113905
ΑN
    Microdefects and impurities in dislocation-free silicon crystals.
ΤI
ΑU
    Abe, T.; Harada, H. (Shin-Etsu Handotai Co., Gunma-ken, Japan); Chikawa,
SO
    Defects in Semiconductors II, Symposium Proceedings
     Editor(s): Mahajan, S.; Corbett, J.W.
    New York, NY, USA: North-Holland, 1983. p.1-17 of xv+582 pp. 26 refs.
     Conference: Boston, MA, USA, Nov 1982
     ISBN: 0-444-00812-8
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- DT Conference Article
- TC Experimental
- CY United States
- LA English

L10 ANSWER 7 OF 7 INSPEC (C) 2005 IEE on STN



- AN 1983:2039012 INSPEC DN A83046938
- TI Swirl defects in float-zoned silicon crystals.
- AU Abe, T. (Shin-Etsu Handotai Co., Gunma-ken, Japan); Harada, H.; Chikawa, J.
- SO Physica B & C (Feb. 1983) vol.116B+C, no.1-3, p.139-47. 28 refs.

Price: CCCC 0378-4363/83/0000-0000/\$03.00

CODEN: PHBCDQ ISSN: 0378-4363

Conference: Proceedings of the 12th International Conference on Defects in

Semiconductors. Amsterdam, Netherlands, 31 Aug-3 Sept 1982

Sponsor(s): IUPAP; European Phys. Soc.; Netherlands' Phys. Soc.; Univ.

Amsterdam

- DT Conference Article; Journal
- TC Experimental
- CY Netherlands
- LA English

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